### DEPARTMENT OF METALLURGICAL AND MATERIALS ENGINNERING

## NATIONAL INSTITUTE OF TECHNOLOGY, TIRUCHIRAPPALLI

COURSE PLAN – PART I				
Name of the programme and specialization	MTech. (Materials Science and Engineering)			
Course Title	MT 660 ADVANCED	MATERIALS PRO	CESSING LABORATORY	
Course Code	MT 660	No. of Credits	2	
Course Code of Pre- requisite subject(s)	Nil			
Session	Jan 2021	Section (if, applicable)	NA	
Name of Faculty	Dr.N.Ramesh Babu	Department	ММЕ	
Email	rameshrohith@ gmail.com (or) nrb@nitt.edu	Telephone No.	2503464 9944932221	
Name of Course Coordinator(s) (if, applicable)	NA			
E-mail	NA	Telephone No	o. NA	
Course Type	Core (M T	ech Lab cours	e)	
Syllabus (approved in BoS)         1. Fabrication of nanostructured coatings by plasma electrolytic processing         2. Mechanochemical synthesis of nanostructured compounds         3. Microwave synthesis of nanosized ceramic powders         4. Diffusion bonding of Materials         5. Equichannel angular processing of materials         6. Cryorolling of materials         7. Vacuum arc melting of materials         8. Spark plasma sintering of materials         9. Microwave sintering of materials         10.In-situ synthesis of metal matrix composites by casting         COURSE OBJECTIVES         The objective of this laboratory course is to provide an insight for the latest developments in materials processing.				
MAPPING OF COs with POs				
Course Outcomes		Programme Outcomes (PO) (Enter Numbers only)		
After the completion of this co	urse, the student wil	l be able to:		

I-7
I-7
I-7,9
-7
-7

## COURSE PLAN – PART II

COURSE TEACHING A	AND LEARNING ACTIVITIES
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Week/Contact Hours	1	opic	Mode of	Delivery
I	1. Fabrication	of nanostructured		
	coatings by	plasma electrolytic	teachi	ing online+
II-IV	processing		Evpo	rimonto i
	2. Microwave	synthesis of nanos	ized	
	ceramic pov	vders	Expos	sure to the
	3. Mechanoch	emical synthesis o	f i	
V-VIII	nanostructu	red compounds	facilities	available at
	4. Diffusion bo	nding of Materials		
	5. Equichanne	l angular processin	g of I	NILI
X-XII	materials			
	6. Cryorolling	of materials		
	7. Vacuum arc	melting of materia	als	
	8. In-situ syntł	esis of metal matr	ix	
XIII-XIV	composites	by casting		
	9. Spark plasm	a sintering of mate	erials	
	10. Microwave	sintering of materi	als	
OURSE ASSESSM	ENT METHODS (s	hall range from 4	to 6)	
No Mode of	Assessment	Week/Date	Duration	% Weightage

S.No.	Mode of Assessment	Week/Date	Duration	% Weightage
1	Assignment-1	Feb last week	-	20
2	Assignment-II	March last week	1h	20
3	Record writing including answers to the review questions	April last week	-	30
4	Final Assessment* Written test	As per Institute schedule	1.5 h	30
*mandatory; refer to guidelines on page 4				

COURSE EXIT SURVEY (mention the ways in which the feedback about the course shall be assessed)

The feedback from students will be assessed based on the questionnaire prepared by the institute and expected attainment to be 75%.

# COURSE POLICY (preferred mode of correspondence with students, compensation assessment policy to be specified)

The students are expected to attend all the classes except for medical reasons. Minimum attendance of 75% is required for writing the semester examination.

#### MODE OF CORRESPONDENCE (email/ phone etc)

The Course Coordinator is available for consultation at any time.

Students can also contact me at any time through phone or by e-mail.

The phone number and email id will be given to the students at the beginning of the course

#### COMPENSATION ASSESSMENT POLICY

Retest will be conducted for the medical reasons
<u>ATTENDANCE POLICY</u> (A uniform attendance policy as specified below shall be followed)

- > At least 75% attendance in each course is mandatory.
- > A maximum of 10% shall be allowed under On Duty (OD) category.
- Students with less than 65% of attendance shall be prevented from writing the final assessment and shall be awarded 'V' grade.

#### **ACADEMIC DISHONESTY & PLAGIARISM**

- Possessing a mobile phone, carrying bits of paper, talking to other students, copying from others during an assessment will be treated as punishable dishonesty.
- Zero mark to be awarded for the offenders. For copying from another student, both students get the same penalty of zero mark.
- The departmental disciplinary committee including the course faculty member, PAC chairperson and the HoD, as members shall verify the facts of the malpractice and award the punishment if the student is found guilty. The report shall be submitted to the Academic office.

The above policy against academic dishonesty shall be applicable for all the programmes.

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ADDITIONAL INFORMATIC	JN		
The Course Coordinator is a	vailable for consultation at any	time.	
Ctudanta con alco contact m	a at any time through phase a		
Students can also contact m	ie at any time through phone of	r by e-mail.	
Relative grading as nor the l	netituta Policy		
Relative grading as per the	nstitute Policy		
FOR APPROVAL	nstitute Policy		
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#### **Guidelines:**

- a) The number of assessments for a course shall range from 4 to 6.
- b) Every course shall have a final assessment on the entire syllabus with at least 30% weightage.
- c) One compensation assessment for absentees in assessments (other than final assessment) is mandatory. Only genuine cases of absence shall be considered.
- d) The passing minimum shall be as per the regulations.

B.Tech. Admitted in				P.G.
2018	2017	2016	2015	
35% or class whichever is g	average/2 reater.	Peak/3 or cl whichever is lov	ass average/2 ver	40%

- e) Attendance policy and the policy on academic dishonesty & plagiarism by students are uniform for all the courses.
- f) Absolute grading policy shall be incorporated if the number of students per course is less than 10.
- g) Necessary care shall be taken to ensure that the course plan is reasonable and is objective.